



BSI Standards Publication

**Surface chemical analysis — Depth profiling —  
Non-destructive depth profiling of nanoscale  
heavy metal oxide thin films on Si substrates  
with medium energy ion scattering**

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## National foreword

This British Standard is the UK implementation of [ISO 23170:2022](#).

The UK participation in its preparation was entrusted to Technical Committee CII/60, Surface chemical analysis.

A list of organizations represented on this committee can be obtained on request to its committee manager.

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### Amendments/corrigenda issued since publication

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*Analyse chimique des surfaces — Profilage d'épaisseur — Profilage  
d'épaisseur non destructif de films minces d'oxydes de métaux lourds  
à l'échelle nanométrique sur des substrats de Si par diffusion d'ions de  
moyenne énergie*

